

SEP. 10 2007

**Docket No.: 020732-97.668 (7493)**

**Appl. No. 10/792,038**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**In re United States Patent Application of:**

**Docket No.: 020732-97.668**  
**(7493)**

**Applicants:** RATH, Melissa K., et al.

**Conf. No.:** 4823

**Application No.: 10/792,038**

**Art Unit: 1752**

**Date Filed: March 3, 2004**

**Examiner:** LE, Hoa Van

**Title: COMPOSITION AND PROCESS FOR POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A SUBSTRATE**

**Customer No.:** 24239

# FACSIMILE TRANSMISSION CERTIFICATE

**Attn: Examiner Hoa Van Le**

**Fax No. (571) 273-8300**

I hereby certify that this document is being filed in the United States Patent and Trademark Office, via facsimile transmission to Mail Stop AF, Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on September 10, 2007, to United States Patent and Trademark Office facsimile transmission number (571) 273-8300.

39

Number of Pages (including cover)

**Tristan A. Fuierer**

**September 10, 2007**

Date \_\_\_\_\_

**AMENDMENT RESPONDING TO JULY 9, 2007 OFFICE ACTION AND SUPPLEMENTAL  
INFORMATION DISCLOSURE STATEMENT IN UNITED STATES PATENT  
APPLICATION NO. 10/792,038**

**Mail Stop AF  
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450**

**Sir:**

**This responds to the July 9, 2007 Office Action in the above-identified application.**